[East & USPB, USPT, WPID, JPO]

		0 11313 131		<u> </u>
L Number	Hits	Search Text	DB	Time stamp
1	2257002	etch\$ or patern\$ or remov\$	USPAT;	2004/09/27 14:38
			US-PGPUB	
2	320983	poly or polysi or polysilicon or polycrystal\$	USPAT;	2004/09/27 14:39
			US-PGPUB	
3	555024	"o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3"	USPAT;	2004/09/27 14:39
İ			US-PGPUB	
4	780283	oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide	USPAT;	2004/09/27 14:39
			US-PGPUB	
5	342723	plasma or sputter\$ or corona or rie or mrie or merie or (glow	USPAT;	2004/09/27 14:40
		with discharg\$) or (reactive with ion)	US-PGPUB	
6	42518	(etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:22
-		polysilicon or polycrystal\$)	US-PGPUB	
7	1739	((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:22
',	1700	polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	2004/03/27 10.22
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or	00-1 01 05	
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))		``-
8	158053	oe or me or overetch\$ or (over with etch\$) or (main with	USPAT;	2004/09/27 14:43
0	130033	etch\$)	US-PGPUB	2004/09/27 14.43
9	0	"o.e." or "m.e."	ł .	2004/00/27 44:40
٦	ا	o.e. or m.e.	USPAT;	2004/09/27 14:40
10	2605060	1-4	US-PGPUB	0004/00/07 44 40
10	3605060	1st or first or (etch\$ or patern\$ or remov\$) st	USPAT;	2004/09/27 14:40
144	2000204		US-PGPUB	0004/00/07 44 44
11	3023301	2nd or (poly or polysi or polysilicon or polycrystal\$) nd or	USPAT;	2004/09/27 14:41
40	044540	second	US-PGPUB	0004/00/07 40 00
12	341513	((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or	USPAT;	2004/09/27 13:29
		patern\$ or remov\$)) same ((2nd or (poly or polysi or	US-PGPUB	
		polysilicon or polycrystal\$) nd or second) with (etch\$ or		
1.0		patern\$ or remov\$))		
13	1739	(((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:31
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	
1		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
	,	with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
	į	(etch\$ or patern\$ or remov\$))))		
14	683313	(1st or first or (etch\$ or patern\$ or remov\$) st) with step	USPAT;	2004/09/27 13:34
			US-PGPUB	
15	416824	(2nd or (poly or polysi or polysilicon or polycrystal\$) nd or	USPAT;	2004/09/27 13:36
		second) with step	US-PGPUB	
16	243140	((1st or first or (etch\$ or patern\$ or remov\$) st) with step)	USPAT;	2004/09/27 13:36
•		with (etch\$ or patern\$ or remov\$)	US-PGPUB	
17	42390	((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or	USPAT;	2004/09/27 13:36
] . [second) with step) with (etch\$ or patern\$ or remov\$)	US-PGPUB	
18	42390	(((1st or first or (etch\$ or patern\$ or remov\$) st) with step)	USPAT;	2004/09/27 13:37
		with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or	US-PGPUB	· • · • · • · • · • · • · • ·
		polysi or polysilicon or polycrystal\$) nd or second) with step)		
		with (etch\$ or patern\$ or remov\$))		
		(-15.14 of patentile of femore))		<u> </u>

				
19	180	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$))) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or polycrystal\$) nd or second) with (etch\$ or patern\$ or polycrystal\$) nd or second) with step) with (etch\$ or patern\$	USPAT; US-PGPUB	2004/09/27 13:37
20	13038	or remov\$))) (dual or two) with step with (etch\$ or patern\$ or remov\$)	USPAT; US-PGPUB	2004/09/27 13:38
21	15	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$)) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$))))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$))	USPAT; US-PGPUB	2004/09/27 13:38
22	65	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$)) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))))) same (oe or me or overetch\$)	USPAT; US-PGPUB	2004/09/27 13:38
23	318	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))))) same ((over with etch\$) or (main with etch\$))	USPAT; US-PGPUB	2004/09/27 13:40

24	479	(((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT,	2004/09/27 13:45
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with	·	
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
		remov\$)) same (((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with step) with (etch\$ or patern\$		
		or remov\$)))) or ((((etch\$ or patern\$ or remov\$) with (poly or		
		polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
i		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or	·	
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		1
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((dual or two) with		
		step with (etch\$ or patern\$ or remov\$))) or ((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		·
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) same (plasma or sputter\$ or corona		
i		or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		•
Ì		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same (oe or me or overetch\$)) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
ļ		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharg\$) or (reactive	•	
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same ((over with etch\$) or (main with etch\$)))		
25	319926	cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or	USPAT;	2004/09/27 14:41
		(hydro with bromic) or (hydrogen with bromide)	US-PGPUB	

26	201	((((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:43
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	1
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		į.
	1	with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or	İ	
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
		remov\$)) same (((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with step) with (etch\$ or patern\$		
		or remov\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or		
	ĺ	polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
	Ì	sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)	1	
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((dual or two) with		
		step with (etch\$ or patern\$ or remov\$))) or ((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
	, =	ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
	ļ	or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)	,	
	1	or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or	1	
	i	polycrystal\$) nd or second) with (etch\$ or patern\$ or		
•		remov\$))))) same (oe or me or overetch\$)) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) same (plasma or sputter\$ or corona		
	İ	or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		•
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
İ		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
ļ		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same ((over with etch\$) or (main with etch\$))))		
ľ		same (cl or "cl2" or "cl.sub.2" or hbr or chlorine or		
	}	hydrobromic or (hydro with bromic) or (hydrogen with		
		bromide))		
27	3069	"over etch\$"	USPAT:	2004/09/27 14:42
1)	US-PGPUB	2004/08/27 14:42
28	411	"main etch\$"		2004/00/27 44:40
		mani otoliw	USPAT;	2004/09/27 14:42
			US-PGPUB	

29	619	(((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:46
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
	1	sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
	1.	or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
		remov\$)) same (((2nd or (poly or polysi or polysilicon or		
	•	polycrystal\$) nd or second) with step) with (etch\$ or patern\$		
		or remov\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or		
	-	polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)	_	
	1	with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
	i l	polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((dual or two) with		
		step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
	}	or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or	i	
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		•
	1	polycrystal\$) nd or second) with (etch\$ or patern\$ or	:	
		remov\$))))) same (oe or me or overetch\$)) or "main etch\$"		

<u> </u>			T		_
30	226	(((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:46	Ì
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB		I
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or			l
		"sio2" or "sio sub 2" or dioxide or monoxide) same (plasma or			l
		sputter\$ or corona or rie or mrie or merie or (glow with			ĺ
		discharg\$) or (reactive with ion))) same ((oe or me or			l
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."			
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)			l
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or			l
		polysi or polysilicon or polycrystal\$) nd or second) with	ì		l
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$			١
		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or			ĺ
		remov\$)) same (((2nd or (poly or polysi or polysilicon or			
		polycrystal\$) nd or second) with step) with (etch\$ or patern\$			ı
İ		or remov\$)))) or ((((etch\$ or patern\$ or remov\$) with (poly or			l
		polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or	1		ĺ
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or			l
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or			ĺ
		sputter\$ or corona or rie or mrie or merie or (glow with			
	ĺ				
		discharg\$) or (reactive with ion))) same ((oe or me or			ĺ
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."			ı
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)			ı
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or			l
		polysi or polysilicon or polycrystal\$) nd or second) with			
r	ļ	(etch\$ or patern\$ or remov\$))))) same ((dual or two) with			
		step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or			
		patern\$ or remov\$) with (poly or polysi or polysilicon or			
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or			
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"			
1		or dioxide or monoxide) same (plasma or sputter\$ or corona			
İ		or rie or mrie or merie or (glow with discharg\$) or (reactive			
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)			
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or			
1		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or			
ſ	*	remov\$)) same ((2nd or (poly or polysi or polysilicon or		[
	ļ	polycrystal\$) nd or second) with (etch\$ or patern\$ or			
		remov\$))))) same (oe or me or overetch\$))			
31	24	((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 13:46	
	l	polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB		
	["o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or	3, 3, 5, 5,		
ľ		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or			
	l	sputter\$ or corona or rie or mrie or merie or (glow with			
]	discharg\$) or (reactive with ion))) same ((oe or me or			
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."	,		
	i	or "m.e.") or (((1st or first or (etch\$) or patern\$ or remov\$) st)			
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or	!		
		polysi or polysilicon or polycrystal\$) nd or second) with			
		(etch\$ or patern\$ or remov\$))))) same ("over etch\$" or "main		,	
	Ì	etch\$")		`	
		ettiia)	i	1	

32	238	((((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT:	2004/09/27 13:47
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	2007/00/21 10:41
	ł	"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or	00-1 01 05	
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."	!	
	,	or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
		remov\$)) same (((2nd or (poly or polysi or polysilicon or	,	
		polycrystal\$) nd or second) with step) with (etch\$ or patern\$. ,	•
	1	or remov\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or		
		polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or	,	
	ĺ	"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
		with (atche or natural or remove)) some ((2nd or (natural		
		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((dual or two) with		
		step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		·
i		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
	·	(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same (oe or me or overetch\$))) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
ĺ	Ī	or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharge) or (corona		
	i	or rie or mrie or merie or (glow with discharg\$) or (reactive with icn))) same ((ac or me or exercise) ar (a) or with icn))		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$))	·	
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or	ì	
	ļ	remov\$)) same ((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same ("over etch\$" or "main etch\$"))	Í	

33	124	(((((((etch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 14:36
		polysilicon or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
1		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		1
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
		or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
ŀ		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with		
		(etch\$ or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
ĺ		or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
		remov\$)) same (((2nd or (poly or polysi or polysilicon or		
ļ		polycrystal\$) nd or second) with step) with (etch\$ or patern\$		•
		or remov\$)))) or ((((etch\$ or patern\$ or remov\$) with (poly or		
		polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))) same ((oe or me or		
		overetch\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
	1	or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
ĺ		with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
		polysi or polysilicon or polycrystal\$) nd or second) with	•	
ł		(etch\$ or patern\$ or remov\$))))) same ((dual or two) with		
		step with (etch\$ or patern\$ or remov\$)))) or ((((etch\$ or		
i	İ	patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
ļ]	ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) same (plasma or sputter\$ or corona		
		or rie or mrie or merie or (glow with discharg\$) or (reactive		
i i	Ì	with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
1	Ì	(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
	ļ	polycrystal\$) nd or second) with (etch\$ or patern\$ or		
		remov\$))))) same (oe or me or overetch\$))) or (((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
1	}	polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
1		or dioxide or monoxide) same (plasma or sputter\$ or corona		
	ł	or rie or mrie or merie or (glow with discharg\$) or (reactive		
		with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
		or (main with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
		(etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or		
		remov\$)) same ((2nd or (poly or polysi or polysilicon or		
		polycrystal\$) nd or second) with (etch\$ or patern\$ or		
`		remov\$))))) same ("over etch\$" or "main etch\$"))) same (cl or		
İ	1	"cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro	•	
		with bromic) or (hydrogen with bromide))		

4 '		ch\$ or patern\$ or remov\$) with (poly or polysi or	USPAT;	2004/09/27 14:
	polysili	con or polycrystal\$)) same ("o2" or oxygen or	US-PGPUB	
	"o.sub.2	2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
	"sio2" o	r "sio.sub.2" or dioxide or monoxide) same (plasma or		
,	sputters	or corona or rie or mrie or merie or (glow with		
		g\$) or (reactive with ion))) same ((oe or me or		
	overetc	h\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
	or "m.e.	") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
	with (et	ch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
1	polysi o	r polysilicon or polycrystal\$) nd or second) with		
	(etcn\$ c	or patern\$ or remov\$))))) same ((((1st or first or (etch\$		
1	or pater	rn\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
	remov\$)) same (((2nd or (poly or polysi or polysilicon or		
	polycrys	stal\$) nd or second) with step) with (etch\$ or patern\$		
	or remo	v\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or		
	polysi o	r polysilicon or polycrystal\$)) same ("o2" or oxygen or		
	"0.sub.2	2" or "o3" or ozone or "o.sub.3") same (oxide or sio or		
	"SIO2" 0	r "sio.sub.2" or dioxide or monoxide) same (plasma or		
	sputter	or corona or rie or mrie or merie or (glow with		
	discharg	g\$) or (reactive with ion))) same ((oe or me or		
	overetch	n\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
İ		") or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
	with (etc	ch\$ or patern\$ or remov\$)) same ((2nd or (poly or		
İ		r polysilicon or polycrystal\$) nd or second) with		
		r patern\$ or remov\$))))) same ((dual or two) with		
	step wit	h (etch\$ or patern\$ or remov\$))) or (((((etch\$ or		
	patern\$	or remov\$) with (poly or polysi or polysilicon or		
ļ	polycrys	tal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
	ozone o	r "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		
Į.	or dioxid	le or monoxide) same (plasma or sputter\$ or corona		
ľ		mrie or merie or (glow with discharg\$) or (reactive		
	with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
	or (main	with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
	(etch\$ o	r patern\$ or remov\$) st) with (etch\$ or patern\$ or		
İ	remov\$)) same ((2nd or (poly or polysi or polysilicon or		
-	polycrys	tal\$) nd or second) with (etch\$ or patern\$ or		
ľ	remov\$))))) same (oe or me or overetch\$))) or (((((etch\$ or		
	patern\$	or remov\$) with (poly or polysi or polysilicon or		
	polycrys	tal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or		
	ozone oi	"o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2"		•
ŀ	or dioxid	e or monoxide) same (plasma or sputter\$ or corona		
		mrie or merie or (glow with discharg\$) or (reactive		
1	with ion))) same ((oe or me or overetch\$ or (over with etch\$)		
	or (main	with etch\$)) or ("o.e." or "m.e.") or (((1st or first or		
	(etch\$ or	r patern\$ or remov\$) st) with (etch\$ or patern\$ or		
	remov\$)) same ((2nd or (poly or polysi or polysilicon or		
1	polycrys	tal\$) nd or second) with (etch\$ or patern\$ or		
	remov\$))))) same ("over etch\$" or "main etch\$"))) not		
	(((((((etc	ch\$ or patern\$ or remov\$) with (poly or polysi or		
	polysilico	on or polycrystal\$)) same ("o2" or oxygen or	•	
	"o.sub.2'	or "o3" or ozone or "o.sub.3") same (oxide or sio or		
	"sio2" or	"sio.sub.2" or dioxide or monoxide) same (plasma or		
	sputter\$	or corona or rie or mrie or merie or (glow with		
	discharg	\$) or (reactive with ion))) same ((oe or me or		
ł	overetch	\$ or (over with etch\$) or (main with etch\$)) or ("o.e."		
	or "m.e."	or (((1st or first or (etch\$ or patern\$ or remov\$) st)		
ľ	with (etcl	n\$ or patern\$ or remov\$)) same ((2nd or (poly or		
	polysi or	polysilicon or polycrystal\$) nd or second) with		
	(etch\$ or	patern\$ or remov\$))))) same ((((1st or first or (etch\$		
	or patern	\$ or remov\$) st) with step) with (etch\$ or patern\$ or		
1	remov\$))	same (((2nd or (poly or polysi or polysilicon or		
	polycryst	al\$) nd or second) with step) with (etch\$ or patern\$		
	or remov	\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or		
	polvsi or	polysilicon or polycrystal\$)) same ("o2" or oxygen or	1	
	"o.sub.2"	or "o3" or ozone or "o.sub.3") same (oxide or sio or		
	"sio2" or	"sio.sub.2" or dioxide or monoxide) same (plasma or		
h History	9/27/04 2:47tH99P	M coRegue or mile or merie or (glow with		
'	discharge	b) or (reactive with ion))) same ((oe or me or	İ	
PS\east\w		ws6 ver ith etch\$) r (m in ith etch\$)) r (" .e."		
	U LODGOHO (CAMMANA)	ruvatu toi isirosojiwa filifili ili Hillima fil 🖴 " 🗀 " 🗎		

35	1618021	etch\$ or patern\$ or remov\$	JPO; DERWENT	2004/09/27 14:39
36	310091	poly or polysi or polysilicon or polycrystal\$	JPO; DERWENT	2004/09/27 14:39
37	335603	"o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3"	JPO; DERWENT	2004/09/27 14:39
38	757669	oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide	JPO; DERWENT	2004/09/27 14:39
39	266706	plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion)	JPO; DERWENT	2004/09/27 14:40
40	0	"o.e." or "m.e."	JPO; DERWENT	2004/09/27 14:40
41	2050890	1st or first or (etch\$ or patern\$ or remov\$) st	JPO; DERWENT	2004/09/27 14:41
42	1876300	2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second	JPO; DERWENT	2004/09/27 14:41
43	279414	cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide)	JPO; DERWENT	2004/09/27 14:42
44	308	"over etch\$"	JPO; DERWENT	2004/09/27 14:42
45	64	"main etch\$"	JPO; DERWENT	2004/09/27 14:42
46	92628	oe or me or overetch\$ or (over with etch\$) or (main with etch\$)	JPO; DERWENT	2004/09/27 14:46
47	1641	(etch\$ or patern\$ or remov\$) with (dual or two) with step	JPO; DERWENT	2004/09/27 14:43
48	23424	(etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)	JPO; DERWENT	2004/09/27 14:44
49	229	((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or	JPO; DERWENT	2004/09/27 14:44
		"sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))		
50	90800	(etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)	JPO; DERWENT	2004/09/27 14:44
51	82237	(etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second)	JPO; DERWENT	2004/09/27 14:45
52	61188	((etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second))	JPO; DERWENT	2004/09/27 14:45
53	27	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) and (((etch\$ or patern\$ or remov\$) with (dual or two) with step) or (((etch\$ or patern\$ or remov\$) with	JPO; DERWENT	2004/09/27 14:45
54	78436	(1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second)))) oe or me or overetch\$ or "over etch\$" or "main etch\$"	IDO	
55	76430		JPO; DERWENT	2004/09/27 14:46
		(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or	JPO; DERWENT	2004/09/27 14:47
		(reactive with ion))) and (oe or me or overetch\$ or "over etch\$" or "main etch\$")		

56		[(-1 # -10#	1	
30	53	(cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or	JPO;	2004/09/27 14:47
		(hydro with bromic) or (hydrogen with bromide)) and (((etch\$	DERWENT	
		or patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or		,
		ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) and (plasma or sputter\$ or corona or		
]	rie or mrie or merie or (glow with discharg\$) or (reactive with		
E 7	1	ion)))		
57	80	((((etch\$ or patern\$ or remov\$) with (poly or polysi or	JPO;	2004/09/27 14:47
		polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2"	DERWENT	
		or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or		
		"sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$		
		or corona or rie or mrie or merie or (glow with discharg\$) or		
		(reactive with ion))) and (((etch\$ or patern\$ or remov\$) with		
		(dual or two) with step) or (((etch\$ or patern\$ or remov\$) with		
	ĺ	(1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$		
		or patern\$ or remov\$) with (2nd or (poly or polysi or		
		polysilicon or polycrystal\$) nd or second))))) or ((((etch\$ or		
		patern\$ or remov\$) with (poly or polysi or polysilicon or		
		polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or		
		ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2"		
		or dioxide or monoxide) and (plasma or sputter\$ or corona or		
		rie or mrie or merie or (glow with discharg\$) or (reactive with		
		ion))) and (oe or me or overetch\$ or "over etch\$" or "main		
	[etch\$")) or ((cl or "cl2" or "cl.sub.2" or hbr or chlorine or		
		hydrobromic or (hydro with bromic) or (hydrogen with		
	<u> </u>	bromide)) and (((etch\$ or patern\$ or remov\$) with (poly or		
		polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or		
		"o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or		
		"sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or		
		sputter\$ or corona or rie or mrie or merie or (glow with		
		discharg\$) or (reactive with ion))))		